

AMENDMENTS TO CLAIMS

1-23. (cancelled)

24. (currently amended) A charged particle beam apparatus comprising:
a charged particle source;

an optical element for adjusting a charged particle beam emitted by the
charged particle source;

an alignment deflector for aligning the axis of the charged particle beam with
respect to the optical element; and

a control device for calculating a two dimensional deviation between images
when said optical element is varied,

wherein said control device determines ~~the direction and amount of~~
~~deflection of said alignment deflector when a predetermined signal is supplied to said~~
~~alignment deflector, and then calculates a signal supplied to said alignment deflector~~
~~based on the determined direction and amount of deflection, such that deviation~~
~~between images becomes zero or nearly zero~~ a condition of the alignment deflector by
varying the condition of the alignment deflector, and then calculates a signal supplied
to the alignment deflector based on the determined condition of the alignment
deflector.

25. (previously presented) The apparatus according to claim 24, wherein said
control device detects a deviation that is detected when the condition of said optical
element is varied, for each different condition of said alignment deflector.

26. (previously presented) The apparatus according to claim 25, wherein said
control device calculates an unknown number indicating the relationship between said

deviation and said alignment condition based on the deviation detected for said each different condition.

27. (currently amended) ~~A charged particle beam apparatus comprising:
a charged particle source;
an optical element for adjusting a charged particle beam emitted by the
charged particle source;
an alignment deflector for aligning the axis of the charged particle beam with
respect to the optical element;
a detector for detecting charged particles; and
a control device for calculating a deviation between images formed on the
basis of the charged particles when the optical element is varied;
wherein said control device determines the direction and amount of
deflection of said alignment deflector when a predetermined signal is supplied to said
alignment deflector, and stores the amount of correction by said alignment deflector,
for each alignment by said alignment deflector The apparatus according to claim 24,
wherein the control device calculates a coefficient determining the condition of the
alignment deflector.~~

28. (currently amended) ~~A charged particle beam apparatus comprising:
a charged particle source;
an optical element for adjusting a charged particle beam emitted by the
charged particle source;
an alignment deflector for aligning the axis of the charged particle beam with
respect to the optical element;
a detector for detecting charged particles; and~~

~~a control device for calculating a deviation between images formed on the basis of the charged particles when said optical element is varied;~~

~~wherein said control device determines whether or not there is structure information necessary for the calculation of said deviation, based on said image~~ The apparatus according to claim 24, wherein said control device determines the direction and amount of deflection of said alignment deflector when a predetermined signal is supplied to said alignment deflector, and stores the amount of correction by said alignment deflector, for each alignment by said alignment deflector.

29. (currently amended) The apparatus according to claim ~~[[28]]~~ 24, wherein said control device ~~quantifies the presence or absence of said~~ determines whether or not there is structure information necessary for the calculation of said deviation ~~[[in]]~~ based on said image.

30. (currently amended) The apparatus according to claim 29, wherein said control device ~~determines that said~~ quantifies the presence or absence of said structure information is ~~not suitable for alignment by said alignment deflector if said quantified value is equal to or lower than a predetermined value~~ necessary for the calculation of said deviation in said image.

31. (currently amended) The apparatus according to claim ~~[[29]]~~ 30, wherein said control device ~~effects quantification by a two-dimensional Fourier transform of said image~~ determines that said structure information is not suitable for alignment by said alignment deflector if said quantified value is equal to or lower than a predetermined value.

32. (currently amended) ~~A charged particle beam irradiating method for irradiating a sample with a charged particle beam emitted by a charged particle beam source via an astigmatism corrector and an objective lens in that order, comprising the steps of:~~

~~effecting an autofocusing by said objective lens;~~

~~adjusting the axis of said charged particle beam with respect to said astigmatism corrector; and~~

~~adjusting the axis of said charged particle beam with respect to said objective lens~~ The apparatus according to claim 30, wherein said control device effects quantification by a two-dimensional Fourier transform of said image.

33. (new) The apparatus according to claim 24, wherein the optical element is an objective lens which focuses charged particle beam and/or an astigmatism corrector which corrects an astigmatism of the charged particle beam.

34. (new) A charged particle beam irradiating method for irradiating a sample with a charged-particle beam emitted by a charged-particle beam source, comprising the steps of:

determining a condition of an alignment deflector by varying the condition of the alignment deflector, and

calculating a signal supplied to the alignment deflector based on the determined condition of the alignment deflector.